



Doctoral School on Materials Sciences and Technologies

Institute of Technical Physics and Materials Science **Centre for Energy Research**

7th Semester Report On

'Optical Calibration of the Multi-Color Ellipsometric Mapping Tool from Cheap Parts '



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1. Introduction

Spectroscopic Ellipsometry (SE)

- Non-destructive, non-invasive and non-intrusive optical technique.
- Measures the relative change in polarization state of the measurement beam.
- The two SE measurable values: Amplitude ratio tan(ψ) and phase difference (Δ) between the p- and s-polarizations.
- ψ and Δ are related to the wavelength of the light beam 'λ' and the angle of incidence of the beam 'θ' at the sample surface, respectively.
- Major Steps: Measurement, Data interpretation, Modelling, Fitting, Evaluation and Results.

1.1. Aim of the Research

 Making an optical mapping tool prototype from cheap parts like:

Tablets, monitors and big screen LCD, LED TV

- Programming the data collection and data processing software.
- Making measurements on selected samples and determining the precision of the prototype.

1.2. Research Methods

Original Concept of Prototype building using different parts

- **1**. Light-source (LED-panel)
- 2. Diffuser sheet
- 3. Film-polarizer
- 4. Analyzer



Fig. 1: Original concept of the

5. Detector non-collimated beam ellipsometer (pin-hole + CCD-detector) and
6. Sample



Fig. 2: New concept of the non-collimated beam

ellipsometer prototype from cheap parts

- 1) Light source2) Vertical polarizer
- 4) Horizontal polarizer 5) Sample
- 7) Pin hole (sub-mm size) and

- 3) Liquid crystal cell
- 6) Sample holder
- 8) Camera sensor

The new concept is without the rotating polarizers



b)

Fig. 3: a) Experimental set up A) Polarization sensitive camera B) Sample + holder C) LCD monitor

b) Schematic structure (CMOS Pregius Polarsens sensor), **NB.** CMOS sensor is Integrated 4-Directional Wire Grid Polarizer

1.3. Characterization methods



Fig. 4: Schematic diagram of the optical interference in an ambient/thin- film/substrate optical model

$$\rho = \tan(\Psi)\exp(i\Delta) = \frac{r_p}{r_s} \qquad (1)$$

$$r_{jk,p} = \frac{N_k \cos\theta_j - N_j \cos\theta_k}{N_k \cos\theta_j + N_j \cos\theta_k} \quad r_{jk,s} = \frac{N_j \cos\theta_j - N_k \cos\theta_k}{N_j \cos\theta_j + N_k \cos\theta_k} \tag{2}$$

$$t_{jk,p} = \frac{2N_j \cos\theta_j}{N_k \cos\theta_j + N_j \cos\theta_k} \quad t_{jk,s} = \frac{2N_j \cos\theta_j}{N_j \cos\theta_j + N_k \cos\theta_k} \tag{3}$$

Monitor correction,

$$Q_{opt} = Q_{meas} * Q_{monitor}$$
 (4)

1.3.1. Rotating Compensator Spectroscopic Ellipsometer (M2000DI)

- Provides fast and very accurate thin film characterization over a wide spectroscopic range.
- Measures film thickness and optical constants on single or multilayer stack.
- Extreme sensitivity for very
- thin over layers even below 1 nm thickness.



Fig. 5: Rotating Compensator Spectroscopic Ellipsometer (M2000DI)

2. Results (Motive for calibration)

30

25

²⁰ ²⁰ ¹⁵

10

Tan (ψ_{Blue})

1.05

1.03

1.00

0.98

0.95

0.93

0.90

0.88

0.85

0.83

0.80

0.78

0.75



Fig. 6: Direct ellipsometric measurement of monitor.



5 10 15 20 25 30 35 40 45 50

x-axis

Fig. 7: A 60nm SiO₂/Si sample $tan(\Psi)$ and $cos(\Delta)$ measurements for RGB spectrum





5 10 15 20 25 30 35 40 45 50 x-axis



0.75

- Each 20 cm diameter oxide sample was placed at six different.
 positions on the 30x30 cm² holder, 51x32 pixel groups of data points.
- Three SiO₂/Si samples with a nominal thickness of 40, 60, and 100 nm are used for the calibration process ,the MSE results are shown below.



Fig. 8: Left: Merged MSE full map ,

Right: Low-MSE pixel map.

 The oxide samples on three different positions, hence a better calibration was done. Below are the common angle of incidence calibration maps.



Fig. 9:Left: Full angle-of-incidence mapRight: Angle of incidence with low-MSE pixels10

The same calibration process resulted in the thickness maps of our calibration oxide samples, merged in a single frame map.



Fig. 10: Thickness maps of SiO_2/Si samples with nominal thickness of 40 nm, 60 nm, and 100 nm (low-MSE areas)



The conventional Wollam M2000 ellipsometer and our noncollimated ellipsometer after correction and is within 1 nm, which is a good agreement.



Fig. 12: Left: 80nm SiO₂ map thickness from Wollam M2000 **Right:** non-collimated, calibrated mapping tool

4. Conclusion

Advantages

- The new prototype is fast imaging and made up of cheap parts
- Ellipsometric data of large areas can be collected around 10 times faster compared to the "traditional" scanning methods.
- Wide mapping area, up to 150cm is possible.
- No moving parts.

Limitations

- Only three wide wavelength bands (RGB) are in action ,which narrows the range of the light band source.
- '0.1 degree' angle uncertainty from the digital angle gauge used in rotation angle of the LCD, which affects incident polarization state of the light.

Semester Activities, Conferences

- The 9th International Conference on Spectroscopic Ellipsometry (ICSE) held in Beijing, China from May 22-28th, 2022. Online Presentation.
- "Carla Camp Graz- the Photonics Career Hub" (Photonics Austria), from 21-23 September 2022, held in the university of Graz, Austria.
- Symposium on Materials Science held on October 5-7, 2022
- "XXXVII Kando Conference 2022", Óbuda University, which was held from 3-4 November 2022
- SPIE Photonics West, held 28 January 2 February 2023 in San Francisco, California, United States, *published the paper*;
- 12th Workshop on Spectroscopic Ellipsometry (WSE), September 19-21, 2023 in Prague, in the Czech Republic.
- Budapest School on Modern X-ray Science 2023 (October 3-6, 2023)
- 26th Spring Wind Conference, held in Miskolc, Hungary, from 5-7 May 2023.
- XL. Kando Conference. KSC2024, November 7-8, 2024.
- Participated in many online Seminars (Eg. Advanced Photonics Webinar: on Vectorial Metrics in Optics", on 14th Dec 2022, Surface Science Discussions 2024 – Programme, January 9-10, 2024, and many others

Publications

Multi-color ellipsometric mapping tool from cheap parts <u>https://doi.org/10.1117/12.2649926</u>

Multi-color ellipsometric mapping tool from cheap parts ISBN: 9789634493204

https://m2.mtmt.hu/api/publication/33751620

 Optical Calibration of a Multi-Color Ellipsometric Mapping Tool Fabricated Using Cheap Parts.
 Photonics 2024, 11(11), 1036

https://doi.org/10.3390/photonics11111036

köszönöm szépen !